

APR 27 2005

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Patent Application Serial No. 10/806,923
Filing Date March 22, 2004
Inventor Weimin Li et al.
Assignee Micron Technology, Inc.
Group Art Unit 2812
Examiner Unknown
Attorney Docket No. MI22-2274
Customer No. 021567
Title: Methods of Depositing Silicon Dioxide Comprising Layers in the
Fabrication of Integrated Circuitry, Methods of Forming Trench Isolation,
and Methods of Forming Arrays of Memory Cells

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3. Cited References (5)

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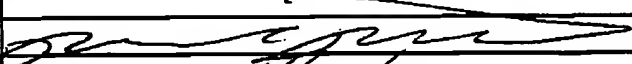
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	Filing Date	March 22, 2004
	First Named Inventor	Welmin Li et al.
	Art Unit	2812
	Examiner Name	Unknown
Total Number of Pages in This Submission	Attorney Docket Number	MI22-2274

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Firm or Individual	Mark S. Matkin, Reg. No. 32,268 Wells St. John, P.S.
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SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

References -- See Attached Form PTO-1449

The attached form PTO-1449 is submitted in compliance with 37 CFR §1.56. Pursuant to 1276 OG 55, August 5, 2003, no copies of cited U.S. patents or U.S. patent application publications are included, as the date of filing of this patent application occurs after June 30, 2003. No admission is made regarding whether all the listed references are prior art.

Respectfully submitted,

Dated: 4-27-05By: 
Mark S. Matkin
Reg. No. 32,268

Sheet 1 of 2

Form PTO-1449	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTORNEY DOCKET NO. MI22-2274	SERIAL NO. 10/806,923
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)		APPLICANT: Weimin Li et al.	
		FILING DATE March 22, 2004	GROUP ART UNIT 2812

U.S. PATENT DOCUMENTS							
*Examiner's Initials		Document Number	Date	Name	Class	Subclass	Filing Date if Appropriate
	AA	6,013,583	1/11/2000	Ajmera et al.			
	AB	2001/0041250 A1	11/2001	Haukka et al.			
	AC	2002/0000195 A1	1/2002	Kao et al.			
	AD	2002/0018849	2/2002	George et al.			
	AE	2003/0032281 A1	2/13/2003	Werkhoven et al.			
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	AG	2004/0209484	10/2004	Hill et al.			
	AH	2004/0265153 A1	12/30/2004	Yongjun Jeff Hu			

FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AI	EP 0817251 A	1/1998	EPO				
	AJ							

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)		
	AK	PCT/US2004/021156; Filed 6/30/2004; Search Report.
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FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AF							
	AG							
	AH							

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)		
	AI	Chen et al., <i>Excimer Laser-Induced Ti Silicidation to Eliminate the Fine-Line Effect for Integrated Circuitry Device Fabrication</i> , 149 JOURNAL OF ELECTROCHEMICAL SOCIETY, No. 11, pp. G609-G612 (2002).
	AJ	Nishiyama et al., <i>Agglomeration Resistant Self-Aligned Silicide Process Using N₂ Implantation into TiSi₂</i> , 36 JPN. J. APPL. PHYS., Part 1, No. 6A, pp. 3639-3643 (June 1997).
	AK	Wolf, <i>Chapter 13: Polycides and Salicides of TiSi_x, CoSi₂, and NiSi</i> , SILICON PROCESSING FOR THE VLSI ERA, Vol. IV, pp. 603-604 (pre-2003).
EXAMINER		DATE CONSIDERED
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